Form PTO 1449  
(Modified)U.S. DEPARTMENT OF COMMERCE  
PATENT AND TRADEMARK OFFICEATTY DOCKET NO.  
217218US2PCTSERIAL NO.  
10/019,278

## LIST OF REFERENCES CITED BY APPLICANT

APPLICANT

Marc DELAUNAY, et al.

FILING DATE

January 2, 2002

GROUP

1762



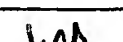
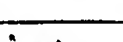
## U.S. PATENT DOCUMENTS

EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
	AA						
	AB						
	AC						
	AD						
	AE						
	AF						
	AG						
	AH						
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	AJ						
	AK						
	AL						
	AM						
	AN						

## FOREIGN PATENT DOCUMENTS

		DOCUMENT NUMBER	DATE	COUNTRY	TRANSLATION	
					YES	NO
	AO					
	AP					
	AQ					
	AR					
	AS					
	AT					
	AU					
	AV					

## OTHER REFERENCES (Including Author, Title, Date, Pertinent Pages, etc.)

	AW	A.Y. Tcherepanov et al, Flat Panel Displays Based Upon Low-Voltage Carbon Field Emitters, 7 <sup>th</sup> International Vacuum Microelectronics Conference, July 1994, vol. 50, pgs. 205-208.	
	AX	D. Hong et al., Field Emission From P-Type Polycrystalline Diamond Films, 7 <sup>th</sup> International Vacuum Microelectronics Conference, Number 271, April 1994, pgs. 96-99.	
	AY	M. Delaunay et al, Electron Cyclotron Resonance Plasma Ion Source for Material Depositions, Review of Scientific Instruments, vol. 69, Number 6, June 1998, pgs. 2320-2324.	
	AZ	Seiichiro Matsumoto, Chemical Vapour Deposition of Diamond in RF Glow Discharge, Journal of Materials Science Letters 4, 1985, pgs. 600-602.	<input checked="" type="checkbox"/> Additional References sheet(s) attached

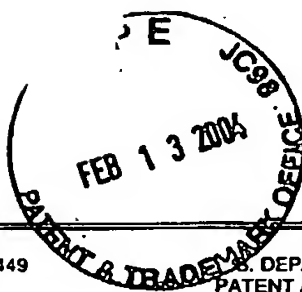
Examiner

*Wes M...*

Date Considered

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SHEET 2 OF 2

Form PTO 1449 (Modified)  U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY DOCKET NO.  217218US2PCT	SERIAL NO.  10/019,278
		APPLICANT  Marc DELAUNAY, et al.	
		FILING DATE  January 2, 2002	GROUP  1762
LIST OF REFERENCES CITED BY APPLICANT			
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	AAA	Jean-Michel Le Corfec, La television du futur se met à plat, Physique Comprendre, April 1998, pg. 87.	
	AAB	Sumio Iijima, Helical Microtubules of Graphitic Carbon, Letters to Nature, Vol. 354, November 7, 1991, pgs. 56-58.	
	AAC	Olivier M. Kuteel, et al., Electron Field Emission From Phase Pure Nanotube Films Grown in a Methane/Hydrogen Plasma, Applied Physics Letters, vol. 73, Number 15, October 12, 1998, pgs. 2113-2115.	
	AAD	Z.P. Huang, et al., Growth of Highly Oriented Carbon Nanotubes by Plasma-Enhanced Hot Filament Chemical Vapor Deposition, Applied Physics Letters, Vol. 73, Number 26, December 28, 1998, pgs. 3845-3847.	
	AAE	Li Yunjun et al, Field Electron Emission From Highly Graphitic Diamond Films With Ball-Like Surface Morphologies, Technical Digest of International Vacuum Microelectronics Conference, Kyomgiu, Korea August 1997, pgs. 137-140.	
	AAF	W.Z. Li et al, Large-Scale Synthesis of Aligned Carbon Nanotubes, Reports, Science, vol. 274, December 6, 1996, pgs. 1701-1703.	
	AAG	M. Delaunay et al., Electron Cyclotron Resonance Plasma Ion Source For Material Depositions, Review of Scientific Instruments, Vol. 69, Number 6, June 1998, pgs. 2320-2324.	
	AAH	Yahachi Saito et al., High Yield of Single-Wall Carbon Nanotubes by arc Discharging Using Rh-Pt Mixed Catalysts, Chemical Physics Letters Vol. 294, September 25, 1998, pgs. 593-598.	
	AAI	S.P. Bozeman et al., Electron Field Emission From Amorphous Carbon-Cesium Alloys, J. Vac. Science Technol. A 15(3), May/June 1997, pgs. 1729-1732.	
	AAJ	A.A. Talin et al., Electron Field Emission From Amorphous Tetrahedrally Bonded Carbon Films, J. Vac. Sci. Technol. A 14(3), May/June 1996, pgs. 1719-1722.	
	AAK	Gehan A.J. Amaratunga et al., Nitrogen Containing Hydrogenated Amorphous Carbon for Thin-Film Field Emission Cathodes, Appl. Phys. Letters 68 (18), 29 April 1996, pgs. 2529-2531.	
	AAL	B.S. Satyanarayana et al., Field Emission From Tetrahedral Amorphous Carbon, Appl. Phys. Letters, 71 (10), 8 September 1997, pgs. 1430-1432.	
	AAM	K. Kuramoto et al., High Quality Diamond Like Carbon Thin Film Fabricated by ECR Plasma CVD, Applied Surfaces Science 113/114 (1997), pgs. 227-230.	
	AAN	W. Zhu et al, Defect-Enhanced Electron Field Emission From Chemical Vapor Deposited Diamond, J. Appl. Phys. 78 (4), 15 August 1995, pgs. 2707-2711.	
	AAO	Takuya Yara et al., Fabrication of Diamond Films at Low Pressure and Low-Temperature by Magneto-Active Microwave Plasma Chemical Vapor Deposition, Jpn. J. Appl. Phys. Vol. 33 (1994) pgs. 4404-4408.	
	AAP	C J Erickson et al., High-Sensitivity Absorption Spectroscopy on a Microwave Plasma-Assisted Chemical Vapour Deposition Diamond Growth Facility, Plasma Sources Sci. Technol. 5 (1996) pgs. 761-764.	
	AAQ		
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